## Characterization of n-on-p detectors with different p-stop and p-spray structures by simulations and measurements

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In this paper the simulation and measurement results of the n-on-p MCz-Si detector structures are described. The five different p-stop and p-spray ion implantation combinations are researched. The combinations are:

- 1) p-stop  $1 \times 10^{15}$  cm<sup>-2</sup> only 2) p-stop  $1 \times 10^{15}$  cm<sup>-2</sup> and p-spray  $1 \times 10^{12}$  cm<sup>-2</sup> 3) p-stop  $1 \times 10^{15}$  cm<sup>-2</sup> and p-spray  $3 \times 10^{12}$  cm<sup>-2</sup> 4) p-stop  $1 \times 10^{15}$  cm<sup>-2</sup> and p-spray  $5 \times 10^{12}$  cm<sup>-2</sup> 5) p-spray  $3 \times 10^{12}$  cm<sup>-2</sup>.

The diodes are electrically characterized by C-V and I-V measurements.

The computer simulations of the n-on-p strip detector are done using Silvaco Virtual Wafer Fab (VWF) software. The cross-section of the n-on-p strip detector is simulated in twodimensions with different dose of p-stop and p-spray. Simulation and measurement results are compared.